L	Hits	Search Text	DB	Time stamp
Number				
1	1072	(hemi\$spher\$4 adj (silicon or Si) or HSG)	USPAT	2004/03/19 12:54
2	578	and capacitor ((hemi\$spher\$4 adj (silicon or Si) or	USPAT	2004/03/19
-	3,3	HSG) and capacitor) and (photo\$1resist or		12:55
		resist or photo\$1sensitive)	USPAT	2004/03/19
3	555	(((hemi\$spher\$4 adj (silicon or Si) or HSG) and capacitor) and (photo\$1resist or	USPAT	10:18
		resist or photo\$1sensitive)) and		
		@ay<=2001		
4	85	((((hemi\$spher\$4 adj (silicon or Si) or	USPAT	2004/03/19
		HSG) and capacitor) and (photo\$1resist or resist or photo\$1sensitive)) and		14:23
		@ay<=2001) and (under\$1cut\$3 or expand or		
		expanding)		
5	920	(hemi\$spher\$4 adj (silicon or Si) or HSG)	US-PGPUB;	2004/03/19 11:26
		and capacitor	EPO; JPO; DERWENT;	11.20
			IBM TDB	
6	252	((hemi\$spher\$4 adj (silicon or Si) or	US-PGPUB;	2004/03/19
		HSG) and capacitor) and (photo\$1resist or	EPO; JPO; DERWENT;	11:26
		resist or photo\$1sensitive)	IBM TDB	
7	157	(((hemi\$spher\$4 adj (silicon or Si) or	US-PGPUB;	2004/03/19
		HSG) and capacitor) and (photo\$1resist or	EPO; JPO;	11:27
		resist or photo\$1sensitive)) and	DERWENT; IBM TDB	
8	24063	<pre>@ay<=2001 capacitor and (photo\$1resist or resist or</pre>	USPAT	2004/03/19
	24003	photo\$1sensitive)		12:55
9	2389	(capacitor and (photo\$1resist or resist	USPAT	2004/03/19
1.0	1 470	or photo\$1sensitive)) and isotropic\$4 ((capacitor and (photo\$1resist or resist	USPAT	12:56 2004/03/19
10	1479	or photo\$1sensitive)) and isotropic\$4)		12:56
		and (side\$1wall or (side adj wall))		
11	1316	(((capacitor and (photo\$1resist or resist	USPAT	2004/03/19
		or photo\$1sensitive)) and isotropic\$4) and (side\$1wall or (side adj wall))) and		12:21
		(plasma or anisotropic\$4)		
12	1206	((((capacitor and (photo\$1resist or	USPAT	2004/03/19
		resist or photo\$1sensitive)) and	1	12:57
		isotropic\$4) and (side\$1wall or (side adj wall))) and (plasma or anisotropic\$4))		
		and (hole or opening or via)		
13	922	(((((capacitor and (photo\$1resist or	USPAT	2004/03/19
		resist or photo\$1sensitive)) and		12:57
		<pre>isotropic\$4) and (side\$1wall or (side adj wall))) and (plasma or anisotropic\$4))</pre>		
		and (hole or opening or via)) and		
		(poly\$1silicon or (poly\$1cryalline adj		
14	900	silicon))	USPAT	2004/03/19
14	892	<pre>((((((capacitor and (photo\$1resist or resist or photo\$1sensitive)) and</pre>	JULIA	12:58
		isotropic\$4) and (side\$1wall or (side adj		
		wall))) and (plasma or anisotropic\$4))		
		and (hole or opening or via)) and (poly\$1silicon or (poly\$1cryalline adj		
		(polysisilicon or (polysiciyaliline adj silicon))) and @ay<=2001		
15	251	((((((capacitor and (photo\$1resist or	USPAT	2004/03/19
		resist or photo\$1sensitive)) and		12:59
		<pre>isotropic\$4) and (side\$1wall or (side adj wall))) and (plasma or anisotropic\$4))</pre>		
		and (hole or opening or via)) and		
		(poly\$1silicon or (poly\$1cryalline adj		
		silicon))) and @ay<=2001) and (etch\$3 adj		
		stop)	L	

			TYODAM	2004/02/10
16	242	<pre>(((((((((capacitor and (photo\$1resist or resist or photo\$1sensitive)) and isotropic\$4) and (side\$1wall or (side adj wall))) and (plasma or anisotropic\$4)) and (hole or opening or via)) and (poly\$1silicon or (poly\$1cryalline adj silicon))) and @ay<=2001) and (etch\$3 adj</pre>	USPAT	2004/03/19 12:59
17	214	stop)) not (((((hemi\$spher\$4 adj (silicon or Si) or HSG) and capacitor) and (photo\$lresist or resist or photo\$lsensitive)) and @ay<=2001) and (under\$lcut\$3 or expand or expanding)) (((((((((capacitor and (photo\$lresist or resist or photo\$lsensitive)) and isotropic\$4) and (side\$lwall or (side adj wall))) and (plasma or anisotropic\$4)) and (hole or opening or via)) and (poly\$lsilicon or (poly\$lcryalline adj silicon))) and @ay<=2001) and (etch\$3 adj stop)) not ((((hemi\$spher\$4 adj (silicon or Si) or HSG) and capacitor) and (photo\$lresist or resist or photo\$lsensitive)) and @ay<=2001) and (under\$lcut\$3 or expand or expanding))) and ((silicon adj nitride) or SiN or	USPAT	2004/03/19 13:00
		"Si.sub.3 N.sub.4" or oxy\$1nitride or		
18	9	SiON) Kwean-Sung-Un.in.	USPAT; US-PGPUB; EPO; JPO;	2004/03/19 14:27
19	18	Hwang-Jae-Seung.in.	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/19 14:27
.mm	1984	capacitor and (photo\$1resist or resist or photo\$1sensitive) and (etch\$1stop or	USPAT	2004/03/18 09:35
_	1984	<pre>(etch\$3 adj stop)) (capacitor and (photo\$1resist or resist or photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and (etch or etching)</pre>	USPAT	2004/03/18 08:23
_	1334	<pre>(capacitor and (photo\$1resist or resist or photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and (sidewall or</pre>	USPAT	2004/03/18 09:32
_	124	(side adj wall)) ((capacitor and (photo\$1resist or resist or photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and (sidewall or	USPAT	2004/03/18 09:52
_	24	(side adj wall))) and (HSG or (hemi\$1spherical adj silicon)) ("5252517" "5364813" "5434812" "5468684" "5497016" "5753547"	USPAT	2004/03/18 08:31
	22	"5885865" "5895250" "5981369" "5985762" "6015734" "6077742" "6080622" "6168985" "6168987" "6194309" "6251790" "6255160" "6268244" "6300192" "6417045" "6436758" "6500763" "6511878" "2001/0018248" "2002/0000596" "2002/0019107" "2002/0028553").PN. ("4636833" "5142438" "5352623" "5362632" "5385863" "5407534" "5447881" "5452178" "5459345" "5486488" "5492850" "5554557" "5612558" "5623243" "5663085" "5963804" "6214688" "6218260" "6258691" "6294437" "6307730" "6319771" "2002/0039826").PN.	USPAT	2004/03/18 09:00

_	292	((capacitor and (photo\$1resist or resist or photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and (sidewall or	USPAT	2004/03/18 09:33
		(side adj wall))) and (transverse\$2 or under\$1cut\$3)		
_	273	<pre>(((capacitor and (photo\$1resist or resist or photo\$1sensitive) and (etch\$1stop or</pre>	USPAT	2004/03/18 09:33
		(etch\$3 adj stop))) and (sidewall or (side adj wall))) and (transverse\$2 or		
		under\$1cut\$3)) not (((capacitor and (photo\$1resist or resist or		
		photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and (sidewall or		
		(side adj wall))) and (HSG or (hemi\$1spherical adj silicon)))		
_	264	((((capacitor and (photo\$1resist or resist or photo\$1sensitive) and	USPAT	2004/03/18 09:34
		<pre>(etch\$1stop or (etch\$3 adj stop))) and (sidewall or (side adj wall))) and</pre>		
	:	(transverse\$2 or under\$1cut\$3)) not (((capacitor and (photo\$1resist or resist		
		or photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and (sidewall or		
		(side adj wall))) and (HSG or (hemi\$1spherical adj silicon)))) and		
_	222	<pre>@ay<=2001 (((((capacitor and (photo\$1resist or</pre>	USPAT	2004/03/18
		resist or photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and		09:38
		(sidewall or (side adj wall))) and (transverse\$2 or under\$1cut\$3)) not		
		<pre>(((capacitor and (photo\$1resist or resist or photo\$1sensitive) and (etch\$1stop or</pre>		
		(etch\$3 adj stop))) and (sidewall or (side adj wall))) and (HSG or		
		(hemi\$1spherical adj silicon)))) and @ay<=2001) and ((silicon adj nitride) or		
		SiN or "si.sub.3 N.sub.4" or oxynitride or siON)		0004/00/10
_	202	<pre>((((((capacitor and (photo\$1resist or resist or photo\$1sensitive) and</pre>	USPAT	2004/03/18 09:40
		<pre>(etch\$1stop or (etch\$3 adj stop))) and (sidewall or (side adj wall))) and</pre>		
		(transverse\$2 or under\$1cut\$3)) not (((capacitor and (photo\$1resist or resist		
		or photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and (sidewall or (side adj wall))) and (HSG or		
		(hemi\$1spherical adj silicon)))) and (@ay<=2001) and ((silicon adj nitride) or		
		SiN or "si.sub.3 N.sub.4" or oxynitride or siON)) not (ink or inkjet)		
_	168	<pre>(((((((capacitor and (photo\$1resist or resist or photo\$1sensitive) and</pre>	USPAT	2004/03/18 09:40
		<pre>(etch\$1stop or (etch\$3 adj stop))) and (sidewall or (side adj wall))) and</pre>		
		(transverse\$2 or under\$1cut\$3)) not (((capacitor and (photo\$1resist or resist		
		or photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and (sidewall or		
		(side adj wall))) and (HSG or (hemi\$1spherical adj silicon)))) and		
		@ay<=2001) and ((silicon adj nitride) or SiN or "si.sub.3 N.sub.4" or oxynitride		
	,	or siON)) not (ink or inkjet)) and (poly\$1silicon or (polycrystalline adj silicon))		
_	143	(capacitor and (photo\$1resist or resist or photo\$1sensitive) and (etch\$1stop or	USPAT	2004/03/18
		(etch\$3 adj stop))) and (HSG or (hemi\$1spherical adj silicon))		
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-	19	((capacitor and (photo\$1resist or resist or photo\$1sensitive) and (etch\$1stop or	USPAT	2004/03/18 09:55
		(etch\$3 adj stop))) and (HSG or (hemi\$1spherical adj silicon))) not		
		(((capacitor and (photo\$1resist or resist		
		or photo\$1sensitive) and (etch\$1stop or		
		(etch\$3 adj stop))) and (sidewall or		
		(side adj wall))) and (HSG or		
	7	(hemi\$1spherical adj silicon))) ("5937314" "5963805" "6037219"	USPAT	2004/03/19
	/	(3937314	USPAI	2004/03/18
		"6174769").PN.		03.00
-	128	crown adj capacitor	USPAT	2004/03/18
		-		09:55
_	115		USPAT	2004/03/18
		(photo\$lresist or resist or		10:02
		photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and (HSG or		
		(hemi\$1spherical adj silicon)))		
_	11	("5391511" "5436188" "5545585"	USPAT	2004/03/18
		"5597756" "5604147" "5821141"		09:56
-		"6043119" "6046093" "6080620"		
		"6107139" "6335552").PN. ("5281549" "5354705" "5405796"		0004/00/10
_	8	"5453403" "5595929" "5597756"	USPAT	2004/03/18
		"5629237" "5686337").PN.		09.57
_	920	(cylindric\$3 or cylinder) adj capacitor	USPAT	2004/03/18
				10:04
_	322	((cylindric\$3 or cylinder) adj capacitor)	USPAT	2004/03/18
		and (photo\$1resist or resist or		10:04
	293	<pre>photo\$1sensitive) (((cylindric\$3 or cylinder) adj</pre>	HCDAM	2004/03/10
	293	capacitor) and (photo\$1resist or resist	USPAT	2004/03/18
		or photo\$1sensitive)) not (((capacitor		10.03
		and (photo\$1resist or resist or		
		photo\$1sensitive) and (etch\$1stop or		
		(etch\$3 adj stop))) and (sidewall or		
		(side adj wall))) and (HSG or		
		<pre>(hemi\$1spherical adj silicon))) or ((capacitor and (photo\$1resist or resist</pre>		
		or photo\$1sensitive) and (etch\$1stop or		
		(etch\$3 adj stop))) and (HSG or		
		(hemi\$1spherical adj silicon))) or (crown		.
		adj capacitor))		
Ann	84	((((cylindric\$3 or cylinder) adj	USPAT	2004/03/18
		capacitor) and (photo\$1resist or resist		10:06
	ĺ	or photo\$1sensitive)) not ((((capacitor and (photo\$1resist or resist or		
		photo\$1sensitive) and (etch\$1stop or		
		(etch\$3 adj stop))) and (sidewall or		1
		(side adj wall))) and (HSG or		
		(hemi\$1spherical adj silicon))) or		
1		((capacitor and (photo\$1resist or resist		
		or photo\$1sensitive) and (etch\$1stop or (etch\$3 adj stop))) and (HSG or		
		(hemi\$1spherical adj silicon))) or (crown		
		adj capacitor))) and (etch\$1stop or		
		(etch\$3 adj stop\$4))		